

TEST PATTERN, INSPECTION METHOD, AND DEVICE MANUFACTURING METHOD

ABSTRACT OF THE DISCLOSURE

In a method according to one embodiment of the invention, aberrations
5 in a lithographic apparatus are detected by printing a test pattern having at
least one degree of symmetry and being sensitive to a particular aberration in
the apparatus, and using a scatterometer to derive information concerning the
aberration. The test structure may comprise a two-bar grating, in which case
the inner and outer duty ratios can be reconstructed to derive information
10 indicative of comatic aberration. Alternatively, a hexagonal array of dots can
be used, such that scatterometry data can be used to reconstruct dot diameters
indicative of 3-wave aberration.